

Abstract

METHODS AND APPARATUS FOR CLEANING DEPOSITION CHAMBER PARTS USING SELECTIVE SPRAY ETCH

In one aspect, a spray cleaning apparatus (400, 500, 600, 700) for components of an electronic device manufacturing process chamber includes: a support member (606, 702, 706); a
5 spray nozzle (408, 608) attached to the support member; a cleaning chemistry supply (410, 604, 704); and a conduit (606, 706) adapted to convey cleaning chemistry from the cleaning chemistry supply to the spray nozzle; wherein the spray nozzle
10 attached to the support member is adapted to rotate and/or to move linearly and is adapted to direct a spray of cleaning chemistry to the interior of an electronic device manufacturing process chamber component from a plurality of directions.

15 (Fig. 6)